

Amendments to the Claims

1-16. (Cancelled)

17. (Currently amended) A low-reflective thin-film substrate comprising:
a thin film formed in multilayer on a transparent glass substrate ~~by sputtering a target material containing,~~
wherein the thin film contains no chromium component and ~~comprising~~ comprises an alloy of ~~Ni and at least one of Ni, Fe and Co and at least one of Mo, W, Ta and Nb~~ Fe, Mo, W and Cu,
and wherein the low-reflective thin-film substrate has a minimum reflectivity which is 0.5% or lower and an optical density of at least 4 at a wavelength in the visible light region.

18. (Previously presented) The low-reflective thin-film substrate of claim 17, wherein the thin film is formed by sputtering under a gas atmosphere of at least one of an inert gas, an oxygen gas, and a carbon oxide gas in a vacuum film-forming apparatus.

19. (Currently amended) The low-reflective thin-film substrate of claim 17, wherein ~~the target material~~ thin film contains at least one of Cu, Ti, Zr and Sn.

20. (Currently amended) The low-reflective thin-film substrate of claim 18, wherein ~~the target material~~ thin film contains at least one of Cu, Ti, Zr and Sn.

21-24. (Cancel)

25. (New) The low-reflective thin-film substrate of claim 17, wherein layers forming the multilayer have different optical properties from one another.